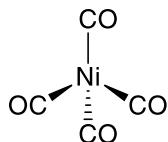


Catalog # 28-1150 Nickel carbonyl



Thermal Behavior:

- Melting point -19.3°C
- Boiling point 43°C
- Vapor pressure: 315 Torr/20°C

Technical Notes:

1. ALD/CVD precursor for Ni thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ni ^{Pwd}	CVD	RT	-	-	60°C	1
Ni	CVD	-25°C	760 Torr	-	60-80°C	2
Fe _x Ni _y	CVD	-9°C	85 Torr	Fe(CO) ₅	175-400°C	3

References:

1. [J. Nanoparticle Res. 2004, 6, 215.](#)
2. [Ann. Chim. Sci. Mat. 2000, 25, 81.](#)
3. [Chem. Vap. Deposirion 1997, 3, 97.](#)